



# TEL Clean Track ACT8 SYSTEM

(RNX20200226-05)

2020.02.26



# TEL Clean Track ACT8 System

## Wafer Specification

<b>Wafer Size</b>	<b>200mm</b>	<b>Description</b>	<b>Coater - Developer</b>
<b>Model</b>	<b>ACT8</b>	<b>Vintage</b>	<b>2002</b>

## System Configuration

**UNC : Uni-Cassette Stage**

**HHP : High Temperature Station**

**ADH : Adhesion Process Station**

**CHP : Chiling**

**COT : Coat Process Station**

**CPL : Cool Plate**

**TRS : Transition Stage**

**DEV : Develop Process Station**

**LHP : Low Temperature Station**

**WEE : Wafer Egde Exposure Process Station**

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## System Configuration

4-4 WEE		3-24 LHP		3-14 LHP	2-24 HHP		2-14 HHP	1-0 CRA	1-4 UNC	
		3-23 CHP		3-13 LHP	2-23 LHP		2-13 LHP			
4-5 EIS	4-0 IRA	3-22 CHP		3-12 CPL	2-22 LHP		2-12 CPL			1-3 UNC
		3-21 CHP		3-11 CPL	2-21 CPL		2-11 CPL			
		3-20		3-10	2-20		2-10			
		3-19 CHP	3-29 LHP	3-9 CPL	2-19 CPL	2-29 LHP	2-09 CPL			
		3-18	3-28 LHP	2-18		2-28 LHP	2-08 TRS			
		3-17 CPL	3-27 LHP	2-17 ADH		2-27 LHP	2-07 TCP			
		3-16 TRS	3-26 LHP	3-6	2-16	2-26 LHP	2-6			
		3-15 TRS	3-25 LHP	3-5 CPL	2-15 ADH	2-25 LHP	2-5 ADH			
4-3 BUFFER		3-0 PRA			2-0 PRA			1-2 UNC		
4-2 BUFFER		3-3 DEV	3-4 DEV				1-1 UNC			
4-1 T. HOLD		3-1 DEV		2-1 COT	2-2 COT	1-5 Pick-Up				

# **TEL Clean Track ACT8 System**

## **System Configuration**

### **External Tool**

- 1). Chemical Cabinet #1 (HMDS, Solvent, Developer)**
- 2). Thermo Controller Unit #1 (SMC)**
- 3). AC Power Box**

### **Machine Detail Information**

#### **2-1). Carrier Station**

- Type : Normal Uni-Cassette Type**
- 4 Cassette Stage, 1 Pick-up Cassette**

#### **2-2). Coater Unit**

- 3 Dispense Nozzle with Temperature Controlled Line for Etch Unit**
- Mini Pump**
- Rinse Nozzle : Back / EBR / Solvent Batch for with Unit**
- Rinse System : 3 Litter 2 Tank Buffer Tank System**
- P. R Suck-Back Valve Type : Air Operation Suck-Back Valve**

# **TEL Clean Track ACT8 System**

## **Machine Detail Information**

### **2-3). Developer Unit**

- H Nozzle for Each Unit**
- 2 Stream Nozzle for DI Rinse and 2 Point for Back Side Rinse on Each Unit**
- Developer System : 3 Liter 2 Tank Buffer Tank System**
- Developer Temperature Control System**
- Drain Direct Drain**

### **2-4). Interface**

### **2-5). Adhesion Unit : 3 Unit**

- 100% Sealing Closed Chamber (Built-in Hot Plate)**
- HMDS Tank with Float Sensor in System**

### **2-6). Low Temp Hot Plate (LHP) : 16ea**

### **2-7). High Temp Hot Plate (HHP) : 2ea**

### **2-8). Chill Plate (CPL) : 10ea**

### **2-9). Chilling Hot Plate Process Station (CHP) : 4ea**

### **2-10). TRS Module : 4ea**

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## Machine Detail Information

**2-11). WEE (Wafer Edge Exposure) Module : 1ea**

**2-12). Chemical Cabinet #1, Solvent & Developer & HMDS**

**2-13). TEMP Control Unit (TCU) 1ea**

**2-14). AC Power Box**

## Missing Parts

**-. 2-1 Nozzle Changer Motor Driver**

**-. PRB2 Z Motor Driver**

**-. 2-0 PRA Motor Driver**

**-. 3-1 ARM 1**

**-. 3-2 ARM 2**

**-. 2-1 Spin I/O Board**

**-. PRB3 X1 Motor Driver**

**-. PRB3 Z Motor Driver**

**-. PRB3 Panasonic Motor Driver 2ea**

**-. IRA Z Motor**

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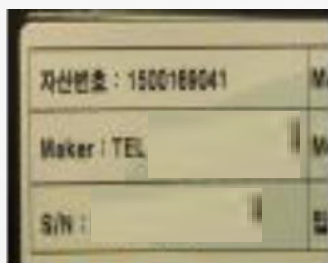
## **Machine Detail Information**

### **Missing Parts**

- . **IRA Y Motor Driver**
- . **IRA X Motor Driver**
- . **Lamp House**
- . **T&H Controller (2 Cup)**
- . **HDD**



# TEL Clean Track ACT8 System



Machine no.



Main Controller



Coater Module (2-1)



Coater Module (2-2)



PRB2 Spin Driver



PR Pump Area



PR Bottle Area



COT Chemical Area(L)



COT Chemical Area(R)



DEV Module (3-1)



DEV Module (3-2)



DEV Module (3-3)



DEV Chemical Area (L)



DEV Chemical Area (R)



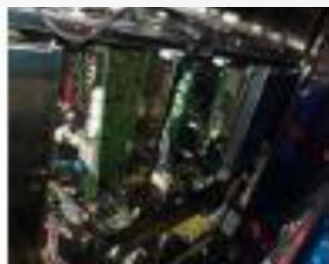
PRB3 Driver Area



# TEL Clean Track ACT8 System



DC Power Box



CSB Board Area



CRA



IRA



HMDS Buffer Tank



CSB & PRB2



PRB3



Chemical Cabinet



Solvent Chemical Area



DEV Chemical Area



InterFace

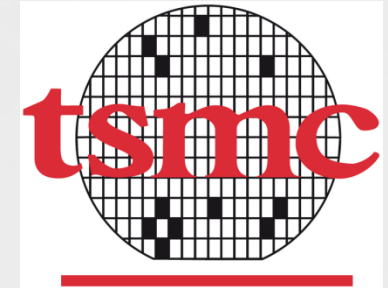


AC Power



Thermo Controller #1

# RenoNix Major Customer



# Contact

We're Capable of Most of service for PVD,CVD, ETCH areas.  
If you have any inquiry or interest , please feel free to contact us.



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